

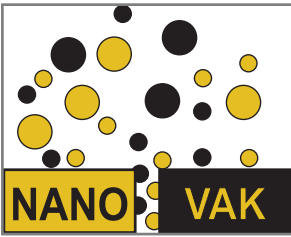
# NANOVAK

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## PECVD System



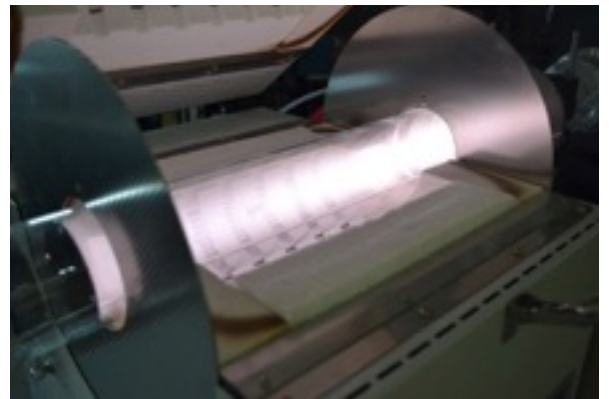
Nanovak Ar-Ge has recently developed PECVD (Plasma Enhanced Chemical Vapor Deposition) tube furnace system, which consists of 300W RF plasma source, optional split tube size furnace, 3 channel mass flow controller unit. It is ideal for TiN, TiC, SiC, Si<sub>3</sub>N<sub>4</sub>, Graphene film production.



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## PECVD System



- 1100 °C furnace temperature for continuous heating
- $\pm 1$  °C PID control of furnace temperature
- Split quartz tube (1000 mm long and 50, 80, 100 mm diameter or as desired)
- Automated PLC controlled vacuum control unit, start-stop vent button
- PC touch screen control option
- Throttle, vent and isolation valves, precise pressure setting, 1 - 100 mTorr
- User defined programmable heating profiles/steps
- 3 channel 0.1 SCCM mass flow controller unit, Ar, N<sub>2</sub>, O<sub>2</sub>, H<sub>2</sub>, CH<sub>4</sub>, NH<sub>3</sub>
- Real time control of all gases, continuous digital display of all gas flows
- Option to add 6 more different gases
- Inductively coupled 300 W 13.56 MHz plasma source
- Quartz sample holder, plasma is confined to the sample zone
- Easy sample load door
- 220V - 16A power requirement
- Closed cycle water cooling
- 75x120 cm footprint, lockable wheels
- Easily passes through the standard doors
- One year warranty for design, materials and workmanship